••	

L Number	Hits	Search Text	DB	Time stamp
1	5295	(250/492.2,504R,492.1).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/26 00:57
2	3764	(extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/09/26 00:58
3	2517	((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/26 01:45
4	494	<pre>(((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:46
5	480	<pre>((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
6	380	(((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
7	111	sample)) and project\$5 ((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
8	74	<pre>(((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode) and collect\$8</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:02
9	12	<pre>((((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern\$4 near1 structure))) and (by-product\$4 or pollut\$5 or contamin\$4 or debris)) and (substrate or wafer or sample)) and project\$5) and electrode) and collect\$8) and (collect\$4 with (by-product\$4 or pollut\$5 or contamin\$4 or debris))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:47
10	222	((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/09/26 01:45

		1777	TICDAM:	2004/00/26
11	193	(((extreme adj ultraviolet) or EUV or	USPAT;	2004/09/26
		extreme-ultraviolet or (extreme adj	US-PGPUB;	01:46
		ultra-violet)) and	EPO; JPO;	
		((250/492.2,504R,492.1).CCLS.)) and (mask	DERWENT;	
		or reticle or (pattern\$4 near1	IBM_TDB	
		structure))	"	
12	79	((((extreme adj ultraviolet) or EUV or	USPAT;	2004/09/26
		extreme-ultraviolet or (extreme adj	US-PGPUB;	01:46
		ultra-violet)) and	EPO; JPO;	
		((250/492.2,504R,492.1).CCLS.)) and (mask	DERWENT;	
		or reticle or (pattern\$4 near1	IBM TDB	
		structure))) and (by-product\$4 or		
		pollut\$5 or contamin\$4 or debris)		
13	4	((((extreme adj ultraviolet) or EUV or	USPAT;	2004/09/26
13	4			01:46
		extreme-ultraviolet or (extreme adj	US-PGPUB;	01.46
		ultra-violet)) and	EPO; JPO;	
		((250/492.2,504R,492.1).CCLS.)) and (mask	DERWENT;	
		or reticle or (pattern\$4 near1	IBM_TDB	
		structure))) and (by-product\$4)		0004/00/06
14	36	(((((((extreme adj ultraviolet) or EUV	USPAT;	2004/09/26
		or extreme-ultraviolet or (extreme adj	US-PGPUB;	02:28
		ultra-violet)) and (mask or reticle or	EPO; JPO;	
		(pattern\$4 near1 structure))) and	DERWENT;	
		(by-product\$4 or pollut\$5 or contamin\$4	IBM_TDB	
	1	or debris)) and (substrate or wafer or		
		sample)) and project\$5) and electrode)		
	ł	and collect\$8) and (plasma with		
		(by-product\$4 or pollut\$5 or contamin\$4		
		or debris))		
15	14	((((((((extreme adj ultraviolet) or EUV	USPAT;	2004/09/26
		or extreme-ultraviolet or (extreme adj	US-PGPUB;	02:29
		ultra-violet)) and (mask or reticle or	EPO; JPO;	
		(pattern\$4 near1 structure))) and	DERWENT;	
į		(by-product\$4 or pollut\$5 or contamin\$4	IBM TDB	
		or debris)) and (substrate or wafer or		
	Ì	sample)) and project\$5) and electrode)		
		and collect\$8) and (plasma with	1	
1		(by-product\$4 or pollut\$5 or contamin\$4	1	l
		or debris))) and		
1		((250/492.2,504R,492.1).CCLS.)	1	
16	3	(((((((((extreme adj ultraviolet) or EUV	USPAT;	2004/09/26
1 10	3	or extreme-ultraviolet or (extreme adj	US-PGPUB;	02:29
1		ultra-violet)) and (mask or reticle or	EPO; JPO;	"2.23
		ultia-violet)) and (mask of relicie of	· ·	
1		(pattern\$4 near1 structure))) and	DERWENT;	ĺ
	1	(by-product\$4 or pollut\$5 or contamin\$4	IBM_TDB	1
		or debris)) and (substrate or wafer or		
	!	sample)) and project\$5) and electrode)		
	1	and collect\$8) and (plasma with	1	
	1	(by-product\$4 or pollut\$5 or contamin\$4		
	<u> </u>	or debris))) and (particle with mov\$6)	L	<u> </u>